



Patent No.: 2328-053

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :
Tuqiang NI et al :
Serial No. 09/821,753 : Group Art Unit: 1734
Filed: March 30, 2001 : Examiner: L. Alejandro
For: PLASMA PROCESSING METHOD AND APPARATUS WITH CONTROLLED
PLASMA EXCITATION POWER

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18103
MW

AMENDMENT

Assistant Commissioner for Patents
Washington, D. C. 20231

Sir:

In response to the October 7, 2002, Office Action, please
amend the referenced application as follows:

IN THE CLAIMS:

Please amend claims 14, 17, 18, 20 and 21 as follows:

14. (Amended) A vacuum plasma processor for processing a
workpiece in a vacuum plasma processor chamber wherein a gas
species is converted into an AC plasma, the chamber being capable
of operating at different pressures while the workpiece is being
processed, the gas species being subject to flowing into the
chamber at different flow rates while the workpiece is being
processed, the processor comprising a reactive element for
supplying an electric field to plasma in the chamber, and an
electric source for supplying gradually changing amounts of power
on a preprogrammed basis to the reactive element.

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